AMENDMENTS TO THE SPECIFICATION

On page 6, please replace the paragraph starting at line 5 with the following:

Fig. 3 is a ~~schematic cross-sectional view~~ piping diagram showing a piping system included in the substrate processing apparatus shown in Fig. 1;

On page 11, please replace the paragraph starting at line 31 with the following:

Discharge pipes 60 are connected to parts of the processing chambers 30A and 30B opposite the parts of the same connected to the main supply pipes 38, respectively. The discharge pipes 60 are connected to a mist trap 61. Exhaust selectors 65, serving as pressure regulating means, are placed in the discharge pipes 60, respectively. Each exhaust selector 65 has a first discharge regulating valve 71 and a second discharge regulating valve 72. A branch pipe 66 and a branch pipe 67 are connected to the outlets of the first discharge regulating valve 71 and the second discharge regulating valve 72, respectively. The first discharge regulating valve 71 allows low-rate discharge when the same is opened. The second discharge regulating valve 72 allows high-rate discharge when the same is opened. At the downstream sides of the discharge regulating valves 72 and 73, the branch pipes 66 and 67 merge into a discharge pipe 60 , which is connected to the mist trap 61. A part of the branch pipe 67 upstream of the second discharge regulating valve 72 is connected, through a branch pipe 81, to a part of the ~~discharge pipe 60~~ discharge pipe 91 downstream of the joint of the branch pipes 66 and 67. Placed in the branch pipe 81 is a third discharge regulating valve 83, which is closed under normal conditions, but opens in emergency, for example, when the pressures in the processing chambers 30A and 30B are excessively high.

On page 22, please replace the paragraph starting at line 16 with the following:

A relief line 220 is connected to the ~~right part~~ left part of the tubular body 175 at a position between the baffle plates 211 and 212. Steam is discharged through the relief line 220 to reduce the internal pressure of the tank 170. Temperature and pressure in the tank 170 can be controlled by discharging steam generated in the tank 170 through the relief line 220 without supplying steam generated in the tank 170 through the main supply pipes 38 to the processing vessels 30A and 30B. Even if the output of the heaters 180 is fixed, the internal pressure of the tank 170 can be decreased, the temperature in the tank 170 can be kept constant and abnormal temperature rise can be prevented by properly discharging steam through the relief line 220. The internal temperature of the tank 170 is kept at about 120°C.

On page 23, please replace the paragraph starting at line 1 with the following:

The drain pipe 201 is provided with a drain valve DV interlocked with the flow regulating valve V3, and a mist trap 227 at the downstream end thereof. The downstream end of the drain pipe 220 is connected to a part, downstream of the ~~flow regulating valve V3,~~ drain valve DV of the relief line 200. The relief line 220 is provided with a flow regulating valve V4 and a shutoff valve V5. A branch pipe 230 is branched from the relief line 220 at a position upstream of the flow regulating valve V4, and is connected to the relief line 220 at a position downstream of the shutoff valve V5. The branch pipe 280 is provided with a relief valve RV1. The mist trap 227 cools deionized water drained through the drain pipe 201 and cools steam discharged through the relief pipe 22 to be condensed, and drains it through the drain pipe 91.

On page 29, please replace the paragraph starting at line 33 with the following:

A manifold supply nozzle 240 as shown in Fig. 18 may be used. The supply nozzle 240 has an ~~inlet part 241~~ inlet part 125 having an inlet end opened in the outer circumference of the circumferential wall 100b and connected to the main supply pipe 38, and five outlet parts 242 passing through the circumferential wall and horizontally radiating out from the inlet part 241 toward the interior of the chamber 30A. Since the outlet parts 242 radiate out into the processing chamber 30A, the process fluid can be supplied radially to diffuse the process fluid efficiently. When forming the supply nozzle 240, a nozzle forming segment 130 is cut out from the circumferential wall 100b, the inlet part 241 is formed in the nozzle forming segment 130 by machining the nozzle forming segment 130 from the side of the convex outer surface 130a, the outlet parts 242 are formed by boring the nozzle forming segment 130 in directions toward the inlet part 241 from the horizontally aligned five parts on the concave inner surface 130b. Then, the nozzle forming segment 130 thus provided with the manifold supply nozzle 240 is fitted in a recess 131 formed in the circumferential wall 100b when the nozzle forming segment 130 is cut out and the nozzle forming segment 130 is welded to the circumferential wall 100b.

On page 35, please replace the paragraph starting at line 26 with the following:

The measuring part 210a has a pipe 210d extending vertically and connected to the upper pipe 210b and the lower pipe 210c, and a level sensor, not shown, attached to the pipe 210d. The level sensor may be provided with a float floating in deionized water contained in the pipe 210d. Alternatively, the pipe 210d may be formed of a transparent material and the level sensor may be an optical level sensor capable of optically detecting the level of deionized water in the pipe 210d. A detection signal provided by the level sensor is sent to a controller, not shown, the controller controls a flow control valve V2 (see Fig. 22) so as to keep the surface L of deionized water contained in the tank 301 at a fixed level. Thus the level of deionized water contained in the tank 301 is controlled by a level regulating means including the controller, not shown, and the flow control valve V2. During the normal operation of the ~~steam generator 301,~~ steam generator 40 the interior of the tank 301 is divided into a lower space where liquid-phase deionized water always exists and an upper space where gas-phase deionized water stage always exist.